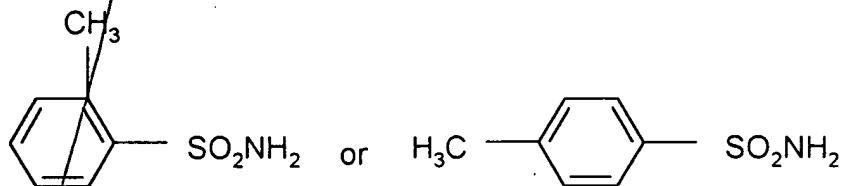


WHAT IS CLAIMED IS:

1. A negative-working photosensitive composition comprising:

- (A) a film-forming polymer
- (B) an unsaturated compound having a radical polymerizable ethylenic double bond,
- (C) a photopolymerization initiator,
- (D) a thermal polymerization inhibitor, and
- (E) at least one member selected from compounds represented by the following formula:



in an amount of 3.5 wt% or less based on the weight of the photosensitive resin composition.

2. The negative-working photosensitive resin composition according to claim 1, wherein the amount of component (E) is in the range of 0.5 - 2.0 wt% based on the weight of the photosensitive resin composition.

3. The negative-working photosensitive resin composition according to claim 1, wherein the amount of component (E) is in

the range of 1.0 - 1.5 wt% based on the weight of the photosensitive resin composition.

4. The negative-working photosensitive resin composition according to claim 1, wherein component (E) is p-toluene-sulfonamide.

5. The negative-working photosensitive resin composition according to claim 1, wherein component (A) is a water-soluble polymer.

EPOCHEMICALS INC.